

*CLAIM AMENDMENTS*

Claims 1-8 (Cancelled).

9. (New) A method of electroplating comprising passing a current having a complex waveform between an electrode and an object being electroplated, the complex waveform alternating between a positive portion and a negative portion, the positive portion comprising a triangular waveform having an initial peak value and that decreases from the peak value at a constant rate, and at least one spike superimposed on the triangular waveform.

10. (New) The method of claim 9 wherein the triangular waveform has an initial current density of substantially 5ASD and the spike has a maximum current density of substantially 11.25ASD.

11. (New) The method of claim 9 wherein the triangular waveform has a period of substantially 1 millisecond.

12. (New) The method of claim 9 wherein the negative portion of the complex waveform has a substantially uniform current density of substantially 12ASD.

13. (New) The method of claim 9 wherein the negative portion of the complex waveform has a period of substantially 1 millisecond.

14. (New) A method of electroplating an object including:  
placing an object to be electroplated in an electroplating bath;  
placing an electrode in the electroplating bath; and  
passing a current having a complex waveform between the object being electroplated and the electrode, the complex waveform alternating between a positive portion and a negative portion, the positive portion comprising a triangular waveform having an initial peak value and that decreases from the peak value at a constant rate, and at least one spike superimposed on the triangular waveform.

15. (New) The method of claim 14 wherein the triangular waveform has an initial current density of substantially 5ASD and the spike has a maximum current density of substantially 11.25ASD.

16. (New) The method of claim 14 wherein the triangular waveform has a period of substantially 1 millisecond.

17. (New) The method of claim 14 wherein the negative portion of the complex waveform has a substantially uniform current density of substantially 12ASD.

18. (New) The method of claim 14 wherein the negative portion of the complex waveform has a period of substantially 1 millisecond.

19. (New) The method of claim 12 including vibrating the object while passing the current between the object and the electrode.

20. (New) The method of claim 12 including agitating the electroplating bath while passing the current between the object and the electrode.